ABSTRACT

5 PROCESS FOR THE FABRICATING AN ELECTRONIC INTEGRATED CIRCUIT AND ELECTRONIC INTEGRATED CIRCUIT THUS OBTAINED

for fabricating an electronic process integrated circuit comprises the formation on 10 substrate (100), of which a part is composed of absorbing material, of a portion (1) made of a sacrificial material. The sacrificial material includes titanium, tantalum, tungsten, nickel, cobalt, molybdenum, gallium, indium, silver, gold, iron and/or 15 chromium. A rigid portion (3,4) is formed in fixed contact with the substrate, on one side of the portion of sacrificial material (1) opposite to the part of the substrate composed of absorbing material. The circuit is heated such that the sacrificial material 20 absorbed into the part of the substrate composed of absorbing material. A substantially empty volume (V) is thus created in place of the portion of sacrificial material (1). Said volume that is substantially empty can replace a dielectric material situated between the 25 electrodes of a capacitor.

Figure 4